¹ Supporting Information

- 2 Quantitative single-molecule study reveals site-
- ³ specific photo-oxidation activities and kinetics on

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17 Section 1. Experimental section

18 Synthesis of the photocatalysts

The g-C₃N₄ was prepared through thermal polymerization of melamine followed by subsequent thermal exfoliation in air.¹ In a typical preparation, 5 g of melamine was put into a covered crucible and then heated to 500 °C for 2 h with a rate of 2 °C min⁻¹. Next, the calcination temperature was increased to 520 °C and maintained for 2 h. The yellow product was ground and 1 g of the product was put in an ark. The powder was evenly spread to a thin layer and put in the muffle furnace. Then it was heated to 520 °C with a ramping rate of 2 °C min⁻¹ and maintained for 6 h. The obtained white product was named as CNS.

26 Materials characterization

27 Transmission electron microscopy (TEM) was conducted on JEOL JEM-2100Plus microscope. Atomic-force microscopy (AFM) images were obtained on Bruker Dimension XR Icon AFM. The 28 29 X-ray diffraction (XRD) pattern was acquired on Bruker D2 Phaser diffractometer with Cu Ka irradiation (λ =1.54184 Å) at 10 mA and 30 kV as the incident beam. Fourier transform infrared 30 (FTIR) spectroscopy was carried out on Perkin-Elmer spectrophotometer (Spectrum 100). 31 Ultraviolet photoelectron spectroscopy (UPS) was conducted on Shimadzu Kratos Axis Supra 32 33 spectrometer equipped with He-I photon source (21.21 eV). UV-vis diffuse reflection spectra 34 (DRS) were collected on the Shimadzu UV-2450 spectrophotometer.

35 Single-molecule fluorescence imaging

The SMF imaging was performed on a total internal reflection fluorescence (TIRF) microscope (Nikon Eclipse Ti-U). In a typical preparation of sample-deposited coverslip, a few drops of catalyst ink (1 mg mL⁻¹) were deposited on the coverslip and fully dried in the oven. Then, a microflow chamber (75.5 mm \times 25.5 mm \times 0.6 mm) was attached to the coverslip and sealed

tightly, which was transferred and fixed on the microscope stage. The Amplex® red (AR) solution 40 was bubbled with N₂ gas for 30 min to remove O₂ in the solution before introduced to the reaction 41 42 chamber. Different concentrations of AR (0.02, 0.05, 0.1, 0.2, 0.5 and 1 µM) solutions were pumped to the chamber with a flowrate of 20 µL min⁻¹. The brightfield images were collected 43 before illumination. The photocatalyst and resorufin were excited by a circularly polarized 405 nm 44 laser (5 mW, L6CC Oxxius) and a 532 nm laser (20 mW), respectively through a quad-edge laser 45 dichroic mirror (Di03-R405/488/532/635-t1-25x36, Semrock). The photoluminescence (PL) 46 signal passed through oil-immersion objective lens (Nikon Plan Apo λ 100×, NA 1.45) and a band-47 pass filter (ET605/70m, Chroma) to reduce the photocatalyst PL signal. Then, the signal was 48 collected by a high-speed electron multiplying charge coupled device (EMCCD) camera (Andor 49 iXon3, 60 Hz). In a typical run, a video composed of more than 30000 frames was recorded and 50 finally processed by the software. 51

52 Computational details

To provide further insights into the photocatalytic activities of different g-C₃N₄ surfaces, DFT 53 calculations with Vienna Ab-initio Simulation Package (VASP)²⁻⁵ were performed for the 54 55 adsorption of AR on BP, wrinkle, and edge. In our calculations, the Perdew-Burke-Ernzerhof (PBE)^{6, 7} functional of the generalized gradient approximation with a plane-wave cut-off energy 56 of 450 eV was used.^{8,9} The basal plane and wrinkle surfaces were based on previous work on g-57 C₃N₄ while the edge was modelled by terminating the N-atoms with hydrogen and adding 10 Å to 58 signify the end of the surface. Optimization calculations were performed using energy and force 59 convergence limits equal to 10⁻⁴ eV per atom and 0.01 eV Å⁻¹ for different surface slabs with 60 explicit dispersion corrections using D3 Grimme's method (DFT-D3).^{10, 11} Geometric constraints 61 62 were applied to both BP and edge g-C₃N₄ surfaces to prevent their corrugation into the more stable

wrinkle structures. The Brillouin zone integration was carried out with a $3 \times 3 \times 1$ Monkhorst-Pack grid for the different surface slabs, and the vacuum height was set to 20 Å between different layers. To optimize AR, the unit cell is set to 20 Å \times 20 Å \times 20 Å to avoid interactions between neighboring molecules and a $1 \times 1 \times 1$ Monkhorst-Pack grid. Several initial locations and configurations of AR on all three surfaces were considered based on symmetry and other important molecular interactions. All the input geometries were optimized and reported in the Supporting Information while the most stable structures in energy are presented here. The adsorption energy (

70 E_{ads}) was calculated according to Eqn. S1

$$71 \quad E_{ads} = -(E_{total} - E_{substrate} - E_{gas - phase adsorbate})$$
(S1)

72 Where E_{total} is the total energy calculated for the substrate with adsorbed reactant or product, 73 $E_{substrate}$ is the calculated energy of the clean substrate, and $E_{gas-phase\,adsorbate}$ is the calculated 74 energy of adsorbed gas phase molecule. To elucidate further the interactions between the adsorbate 75 and substrate, the change of charge densities was quantified using Bader charge analysis.¹²⁻¹⁴

77 Section S2. Morphology and physicochemical properties of CNS.

The phase structure of CNS was characterized by XRD as shown in Fig. S1a. The (002) plane 78 of $g-C_3N_4$ is identified by the diffraction peak at 27.5°, which is attributed to the interplanar 79 periodic stacking of aromatic rings.¹⁵ The low-angle peak at around 13° which is related to the in-80 plane packing of tri-s-triazine motifs is absent in our result. This is probably due to the decrease 81 82 of planar size during the thermal etching process. FTIR spectra were collected to further verify the CNS structure (Fig. S1b). The broad band between 3000 and 3600 cm⁻¹ is ascribed to the stretching 83 mode of N-H bonds. The peaks in the range of 1100 and 1650 cm⁻¹ correspond to the aromatic 84 85 heterocycle stretching.¹⁶ The vibrational bending of triazine rings accounts for the absorption peak at 808 cm⁻¹.¹⁷ The morphology and structural features of CNS are revealed in the TEM images. In 86 Fig. S2a, CNS exhibits an ultrathin and graphene-like structure with great tunability and 87 flexibility. The thickness is measured to be ~9.5 nm by AFM (Fig. S3). The rough surface of CNS 88 is observed, which is caused by the decomposition of polymeric melon units in the g-C₃N₄ planar 89 structure.¹⁸ Besides, the wrinkle structure is formed by folding or bending of BPs (Fig. S2a,b), 90 which reduces the surface energy of CNS. UV-vis DRS and UPS spectra were recorded to study 91 the optical properties of CNS. In Fig. S2c, the bandgap energy of CNS is determined to be 3.0 eV 92 93 by the Tauc plot (inset of Fig. S2c). The slight enhanced absorption in the visible light region is probably due to the multiple scattering effect caused by the porous nature of CNS.¹⁹ The valence 94 95 band (VB) potential of CNS was determined by UPS. As shown in Fig. S2d, the VB maximum is 96 determined to be 1.85 eV and thus the conduction band (CB) minimum of CNS is calculated to be -1.15 eV (inset of Fig. S2d). The relative positive VB position of CNS provides sufficient 97 98 oxidation potential for compound photodegradation, which contributes to the pollutant removal 99 and environmental purification.



101 Fig. S1 (a) XRD patterns and (b) FTIR spectra of CNS.



105 Fig. S2 Morphology and optical properties of CNS. (a, b) TEM images, (c) UV-vis DRS spectra
106 (inset: Tauc plot) and (d) UPS spectra (inset: energy level diagram for bandgap analysis) of CNS.





116 Section S3. SMF study of site-specific catalytic activities, dynamics.

117 The non-fluorescent AR was used as probe molecules to detect h⁺ and study the catalytic heterogeneities on wrinkles, edges and BPs of CNS (Fig. S4). The kinetic steps including reactant 118 absorption, conversion, product dissociation and temporal activity fluctuations are quantified on 119 120 such structures. Upon laser excitation (405 nm), AR can be photo-oxidized via an indirect way by •OH radicals produced from the reaction of h⁺ and OH⁻ in water.²⁰ The product molecule, resorufin 121 is photoexcited by the 532 nm laser and the emitted fluorescence signal is collected by the EMCCD 122 camera with high sensitivity. Hence, in Fig. S5a, the bright dots (in yellow circles) represent the 123 formation of fluorescent resorufin molecules on CNS. 124

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127 Fig. S4 Schematic of the photocatalytic process under the TIRF microscope.

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132 Fig. S5 (a) A single frame of fluorescent bursts (in yellow circles) on CNS. (b) The calculation of

133 spatial resolution using 2D Gaussian fitting (inset: the area from the green square in (a)).



- 136 Fig. S6 (a, c, e) The bright-field images and (b, d, f) corresponding density maps (bin size: 30 nm
- $\,\times$ 30 nm) of CNS with AR. Scale bar: 1 $\mu m.$

Section S4. Determine the localization precision of SMF imaging. 140

Based on the previous works,^{21, 22} the localization precision can be determined by fitting the 141 fluorescence intensity with 2D elliptical Gaussian functions (Eqn. S2, Fig. S5b): 142

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$$I(x,y) = A + B * exp^{[10]}(-(\frac{(x-x_0)^2}{2S_x^2} + \frac{(y-y_0)^2}{2S_y^2}))$$
(S2)

where (x_0, y_0) is the center position, A is the background level, B is the peak intensity at (x_0, y_0) , 144 145 S_x and S_y are the standard deviations of the Gaussian distribution along the x- and y-axes, 146 respectively. The localization precision $(\sigma_j, j=x, y)$ can be calculated using Eqn. S3:

$$\sigma_j = \sqrt{\left(\frac{S_j^2}{N} + \frac{a^2/12}{N} + \frac{8\pi S_j^4 b^2}{a^2 N^2}\right)}$$
(S3)

148 where N is the photons collected, a is the pixel size, and b is the background noise in photons. For the fluorescent burst in the inset of Fig. S5b, the parameters are calculated to be $S_x = 143$ nm, 149 $S_y = 164 \text{ nm}, a = 160 \text{ nm}, N = 660, b = 13, \sigma_x = 14 \text{ nm} \text{ and } \sigma_y = 18 \text{ nm}.$ Thus, the average localization 150 precision is calculated to be $\sigma_{xy} = 16$ nm using Eqn. S4: 151 $\sigma_{xxy} = (\sigma_x + \sigma_y)/2$ 1 60 4)

$$152 \quad \sigma_{xy} = (\sigma_x + \sigma_y)/2$$
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154 Section S5. Image segmentation.

155 To determine the size of reaction subregions, image segmentation was carried out. As shown in 156 Fig. S7b,c, the cross-profiles on the wrinkle and edge are obtained from the marked rectangles in 157 Fig. S7a. The intensity-position profiles are fitted with Gaussian function to obtain the FWHM. The averaged FWHM for the wrinkle and edge profiles are determined to be 164 and 154 nm, 158 159 respectively (Table S1). Such values are close to the size of one pixel (160 nm). Thus, the sizes of 160 the subregions for wrinkles and edges are 1×1 pixel (160 nm \times 160 nm). Besides, we make sure 161 that each subregion contains one fluorescent burst. Otherwise, the size along the wrinkle or edge 162 is reduced (e.g., 100 nm \times 160 nm) to meet this criterion. Regarding the BPs, we also use the 163 subregion size of 160 nm \times 160 nm for convenience with one fluorescent burst in a subregion.



166 Fig. S7 (a) Image segmentation of wrinkles and edges in the density map. Cross-profiles of number
167 of products fitted by Gaussian function at the (b) wrinkle (position 2) and (c) edge (position 3)
168 marked in (a).

5 Positions 1 2 3 4 Average Wrinkle 198 164 160 178 137 145 FWHM (nm) Edge FWHM 130 186 144 158 151 154 (nm)175 176 177 b а Energy С CNS TS CS Basal TS Energy plane СВ СВ TS VB Basal cs CS VB plane CS -► TS \oplus \oplus h+ 0 Strain Type-l d е CS Edge CNS CNS Energy Energy СВ e СВ Vacancy state VB (+) $(\mathbf{+})$ VB $\oplus \oplus$ h+ $(\mathbf{+})$ Ŧ h+ Type-II 178

174 **Table S1.** The FWHM of cross-profiles of number of products at wrinkle and edge positions.

179 Fig. S8 (a) Schematic of wrinkle formation and strain distributions in wrinkles. (b) The
180 dependence of CB and VB positions on the CS and TS present in the structure. Schematic of band
181 modulation with presence of (c) TS in wrinkles, (d) CS in wrinkles and (e) vacancies in edges.

183 Section S6. SMF study of temporal activity fluctuations.

184 To study the temporal variation of reaction rates, the number of single turnovers per unit time 185 (turnover rates) was analyzed based on the trajectories (Fig. S9a). The activity fluctuation is related to the perturbation in chemical reaction (τ_{off}), product dissociation (τ_{on}) or both, known as catalysis-186 induced activity fluctuations.²³ The autocorrelation functions, $C_{\tau}(m) = \langle \Delta \tau(0) \Delta \tau(m) \rangle / \langle \Delta \tau(0)^2 \rangle$, can be 187 used to analyze the effect of τ_{off} and τ_{on} on fluctuations, where $\Delta \tau(m) = \tau(m) - \langle \tau \rangle$, τ represent τ_{off} or 188 τ_{on} and *m* is the index number.^{24,25} As shown in **Fig. S9b,c**, $C_{\tau_{off}}$ and $C_{\tau_{on}}$ show an exponential decay 189 with m, suggesting the fluctuations exist in both τ_{off} and τ_{on} reactions. The corresponding 190 191 correlation time is calculated by multiplying the fitted decay constant (from Fig. S9b,c) by the average turnover time (from Fig. S9a). Thus, the correlation times for τ_{off} and τ_{on} reactions in Fig. 192 **S9b,c** are calculated to be 6.6 and 1.9 s, respectively. The histogram distributions of correlation 193 times (from > 30 locations) are shown in the insets of Fig. S9b,c. 194



196 **Fig. S9** (a) A single-turnover trajectory from the BP calculated based on every 10 turnovers. 197 Autocorrelation functions of (b) τ_{off} and (c) τ_{on} reactions obtained from (a). Insets: Histogram 198 distribution of correlation times calculated from > 30 subregions.

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203 Fig. S10 Cross correlation function of τ_{off} and τ_{on} from the trajectory in Fig. S9a.

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205 Section S7. AR adsorption on BP, wrinkle, and edge surfaces by DFT simulation.

In the figures below, the initial and corresponding optimized geometries of AR on different surfaces of $g-C_3N_4$ are presented in **Fig. S11-S13**. The initial positions of adsorbed species on the surfaces affect the final adsorption geometries as well as the energies, thus we started with nine initial positions to try to cover the most plausible interactions of adsorbate molecule on the surfaces.

211 We also performed Bader charge analyses to study the change in charge density and quantify the amount of charge transfer between different CNS structures and AR. We found Bader charges 212 213 of 0.006, 0.036, and 0.013 e to be transferred from AR onto BP, edge, and wrinkle surfaces, respectively. Despite the relatively weaker adsorption energies, there is definite charge transfer 214from AR to the wrinkle and edge CNS surfaces. As a result, an inbuilt electric field directed from 215 216 AR to edge and wrinkle is generated at the interface, which enables better separation of photoelectron-hole pairs and enhances photocatalytic activity.²⁶ More electron transfer observed 217 218 on the edge and wrinkle indicate better charge separation and faster oxidation of AR on these structures. These electron transfer values are quantitatively low since they are calculated in the 219 ground state; thus, we recommend further material simulations that could unravel the photoactivity 220 221 of CNS surfaces upon light activation.



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Fig. S11 Optimized geometries of AR on BP surface. Structures I-VIII are flat-on configurations while structure IX is a T-shaped configuration. The most stable structure (VIII) was taken as the final adsorption geometry of AR on BP surface as reported in the manuscript.



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Fig. S12 Optimized geometries of AR on edge surfaces. Structures I-VIII are flat-on configurations while structure IX is an edge-on configuration and X as side configuration. The most stable structure (VII) was taken as the final adsorption geometry of AR on edge surface as reported in the manuscript.



Fig. S13 Optimized geometries of AR on wrinkle surface with top (left) and side (right) views. Structures I-VIII are flat-on configurations while structure IX is an edge-on configuration. The most stable structure (VI) was taken as the final adsorption geometry of AR on wrinkle surface as reported in the manuscript.

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